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## Size Distribution in Self Assembled Solid State Si Quantum Dots

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**Abstract:** In the previous work, a model was proposed to quantitatively explain the PL spectrum of colloidal Si quantum dot (QD) by inducing the quantum confinement effect and particle size distribution. In this work, this method is adapted for size distribution analysis of QDs in a solid matrix. Results shows that the size distribution of QDs in these solid samples is more widely spread compared to colloidal one. The possible reason is the lack of constraint in horizontal directions in these samples and thus the QDs become ellipsoidal. The wide distribution of QD size will cause the spread of bandgap and reduce the quantum confinement effect which limits the practical application of such materials.

**Key words:** silicon quantum dots; size distribution; photovoltaics; photoluminescence

## 自组装固体硅量子点中的粒径分布

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**摘要:** 提出了一个用来定量分析胶体硅量子点光致荧光光谱的模型, 得到量子点的粒径分布, 并将此方法应用于固体硅量子点材料粒径分布的分析。结果表明: 与胶体硅量子点相比, 固体样品中硅量子点粒径分布更宽。这可能是由于固体样品硅在结晶过程中水平方向缺乏约束, 因此形成的量子点为椭圆形。纳米硅中粒径分布太宽会导致材料带隙分布变宽。减少量子约束效应, 限制了这些材料在实际中的应用。

**关键词:** 硅量子点; 粒径分布; 光伏; 光致荧光

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Si nanocrystals (Si NCs) or interchangeably quantum dots (QDs) embedded in an oxide matrix are promising materials for all-Si nanostructure tandem solar cells or selective contacts for hot carrier solar cells<sup>[1-4]</sup>. To realize such efficient photonic devices, a tight control over size and a narrow size distribution are necessary. Zacharias et al proposed an effective method to preparing superlattice structure with Si QD<sup>[5]</sup>. Alternating thin layers of a SiO<sub>2</sub> followed by a silicon-rich oxide (SRO) are deposited onto a suitable substrate. This structure may be referred to as “SRO/SiO<sub>2</sub> multilayers”<sup>[6]</sup>. The thickness of each thin layer is in order of a few nanometers. The samples are then annealed at 1100 °C in N<sub>2</sub> atmosphere for 1 hour. The size of such QDs are expected to correspond with the thickness of SRO layer as their growth is constrained by the SRO layer. Such Si QDs have been fabricated by co-sputtering deposition of silicon rich layers interspersed with stoichiometric SiO<sub>2</sub> layers<sup>[2,6]</sup>. Even for this synthesis method, the size distribution of QDs cannot be avoided and should be studied. However, the size distribution of Si QDs embedded in a matrix is very difficult to obtain, considering their non-uniform shapes and remarkable difficulties in TEM imaging<sup>[5,7-9]</sup>. In the previous work, we propose a model to quantitatively explain the PL spectrum of colloidal Si QDs by inducing the quantum confinement effect and particle size distribution. The size distribution information of Si QDs can be extracted from PL fitting naturally<sup>[10]</sup>. This model provides a reliable and non-destructive method and thus in this work we apply it to analyse the size distribution of QDs in a solid matrix.

## 1 Experimental Details

To investigate the effect of silicon quantum dots size distribution, 3 samples with various multilayer structures are fabricated. Alternating SiO<sub>2</sub> and Si rich oxide (SRO) layers were deposited on quartz substrate using an AJA ATC-2200 sputtering system with RF power sources. The Si volume ratio in SRO layer was controlled at 70% by adjusting the RF power applied to the Si and SiO<sub>2</sub> targets. Ar flow rate and chamber pressure during the sputtering process were maintained at 15 sccm and 1.5 m Torr respectively. Sample A and Sample B are monolayer structure which consist 1 SRO/SiO<sub>2</sub> bilayer with thickness of SRO layer 3 nm and 4 nm respectively. Sample C is multilayer structure which consists 30 SRO/SiO<sub>2</sub> bilayers with thickness of SRO layer 4 nm. The thickness of SiO<sub>2</sub> layer of all these samples is 2 nm. The data of reference colloidal Si QD sample are from our previous report.<sup>[11]</sup> PL measurements were performed at room temperature using a semiconductor laser with 405 nm wavelength through an OD 3.5 attenuator and the full power of the laser was 25 mW before attenuation. The semiconductor is still non-degenerated under such illumination<sup>[11]</sup>.

## 2 Results and Discussion

Figure 1 shows the PL spectra of these samples. It can be seen that the peak position of PL has an obvious blue shift as the dot sizes decreases. Such tunability of emission peak can be explained by the quantum confinement effect. Compared with bulk material, the breadth of the PL peak increases which can be explained by the size distribution of the dots. The size distribution causes a distribution of bandgap that broadens the PL spectrum<sup>[11]</sup>.

Under the illumination condition in this experiment, the PL emission is dominated by spontaneous emission. As a result, we only need consider the spontaneous emission  $R_{sp}$  in this PL model as below

$$\begin{aligned} R_{sp}(\hbar\omega) &= D(\hbar\omega) \sum_{a,b} B_{a \rightarrow b} N_a N'_b \delta(E_a - E_b - \hbar\omega) \\ &= D(\hbar\omega) \iint B_{a \rightarrow b} n_a n'_b \delta(E_a - E_b - \hbar\omega) dE_a dE_b \end{aligned} \quad (1)$$

Where  $D(\hbar\omega) = \frac{n^3(\hbar\omega)^2}{\pi^2 \hbar^3 c_0^3}$  is the number of states per unit energy range,  $n$  is the refractive index,  $c_0$  is the velocity of light in vacuum.  $N_a, N'_b$  are the electron and hole occupation number at energy level  $a$  and  $b$  respectively,  $n_a n'_b$  is the density of states of the electron-hole pairs.  $B_{a \rightarrow b} = \frac{4\pi^2 e^2}{m^2 n^2 \omega} |\langle a | \hat{p} | b \rangle|^2$ , is linked to the optical transition matrix element  $|\langle a | \hat{p} | b \rangle|^2$

Under non-degeneration condition, the PL intensity energy  $I(\omega)$  can be expressed as:

$$I(\hbar\omega) \propto \int_0^{\hbar\omega} (\hbar\omega - E_g)^2 (\hbar\omega)^2 e^{-\frac{\hbar\omega}{kT}} e^{\frac{\Delta F}{kT}} \cdot f(E_g) dE_g \quad (2)$$

Where  $k$  is the Boltzmann constant,  $E_g$  is bandgap,  $\hbar\omega$  is the emitted photon energy.  $\Delta F = E_{Fn} - E_{Fp}$  and  $E_{Fn}$  is the electron quasi Fermi energy and  $E_{Fp}$  is the hole quasi Fermi energy,  $f(E_g)$  is the probability density function (PDF) of the bandgap. Since we adopted a log-normal size distribution for nanoparticles, the bandgap distribution function can be obtained as explained below<sup>[11-13]</sup>

$$f_{EG}(E_g) = \frac{1}{\sigma \left( \frac{C_1}{E_g - E_{g\_bulk}} \right)^{\frac{1}{2}} \sqrt{2\pi}} \exp \left( - \frac{(\ln \left( \left( \frac{C_1}{E_g - E_{g\_bulk}} \right)^{\frac{1}{2}} \right) - \ln(d_0))^2}{2\sigma^2}} \right) \cdot \frac{1}{2} \cdot C_1^{\frac{1}{2}} \cdot (E_g - E_{g\_bulk})^{-\frac{3}{2}} \quad (3)$$

Where  $d_0$  is the geometric mean and  $\sigma$  is the geometric standard deviation of the QD diameter.  $E_{g\_bulk}$  is the bandgap of the bulk material,  $d$  is the diameter of nanocrystals and  $C_1$  is a coefficient lumping all other parameters for the quantum confinement effect and use  $2 \text{ eV} \cdot \text{nm}^2$  here<sup>[1,14-15]</sup>.

Using Eq.1 and Eq.2, we can fit the PL spectrum by adjusting  $d_0$  and  $\sigma$ . The detailed fitting parameters are shown in Table 1. The best fits are shown in Figure 1. From the PL spectra fitting, the QD size distribution histogram of these sample can be extracted by log-normal distribution function

$$f_D(d) = \frac{1}{\sigma d \sqrt{2\pi}} \exp \left( - \frac{(\ln d - \ln d_0)^2}{2\sigma^2} \right) \quad (4)$$

**Table 1 Size distribution of Si QD Samples**

Samples	Structure	O/Si ratio in SRO layer	$d_0/\text{nm}$	$\sigma$	Down boundary of 95% confidence interval/nm	Up boundary of 95% confidence interval/nm
A	3 nm, 1 layer	0.7	3.20	0.37	1.74	5.87
B	4 nm, 1 layer	0.7	3.95	0.45	1.89	8.26
C	4 nm, 30 bilayers	0.7	4.10	0.54	1.69	9.94
Reference sample	colloidal		3.70	0.20	2.66	5.11

These histograms are shown in Figure 2.

The size distribution for all samples is shown in Figure 2. It can be seen that the central position for each sample are 3.2 nm, 3.95 nm and 4.1 nm respectively, which correspond with the SRO thickness. Sample B and Sample C have the same SRO layer composition but different number of bilayers. The central position of these two samples are close to their SRO thickness. However, the spread becomes wider as the number of layer increases. For sample B, the size of 95% of the QDs is located between 1.74 nm to 5.87 nm, while for sample C, the size of 95% of the QDs is between 1.69 nm and 9.94 nm. This may be because in the multilayer system, the crystal easily penetrates the 2 nm barrier and from lager grain in the formation process. Moreover, the distribution has an obvious skewness which means the QD size is not evenly distributed and spread more in the large size side. Due to the relation between the bandgap and QD size, the quantum confinement effect will be reduced for the larger crystals. This can be seen in the normalized bandgap distribution in Figure 4.

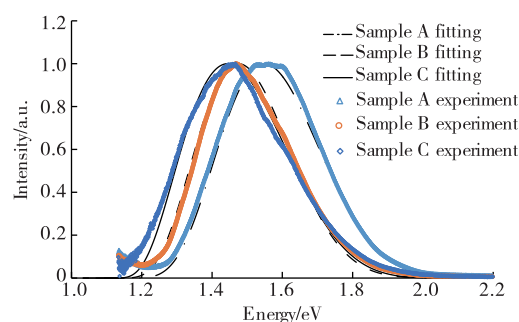


Fig.1 Experimental PL data and fitting

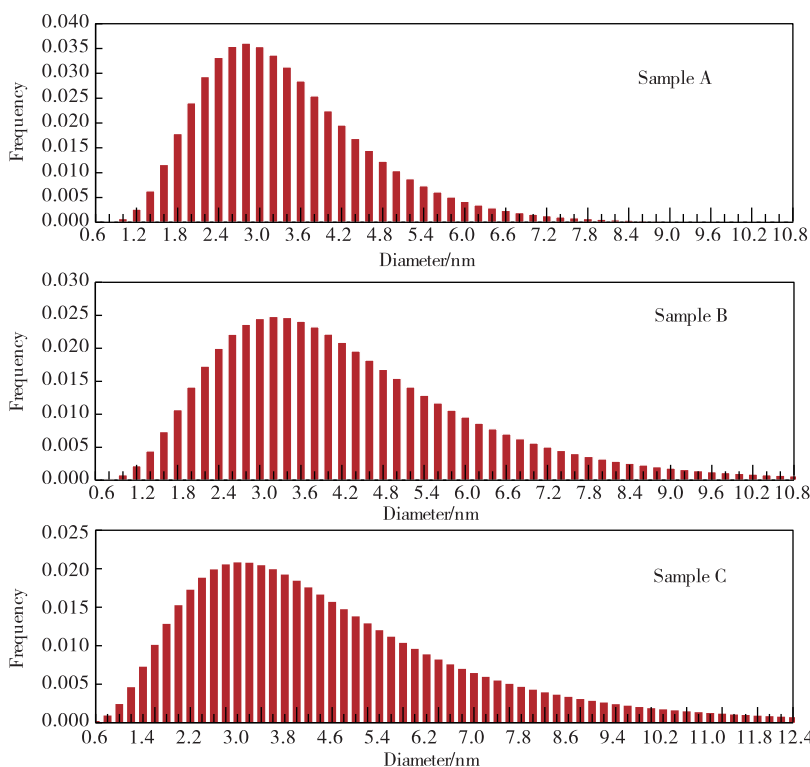


Fig.2 Histograms of the Si QD size from PL fitting

In addition, it can be seen that all these solid state Si QD samples have a wider size distribution compared with colloidal sample, which has negative effects on their practical application. This may be because in thicker SRO layer, the silicon nanocrystal has more space to grow in the horizontal direction and the QD becomes ellipsoidal. This can be seen from the high resolution TEM image of the

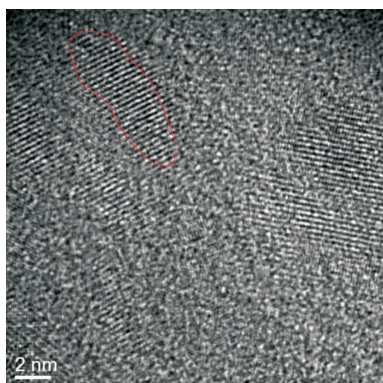


Fig.3 High resolution TEM of annealed Si QDs

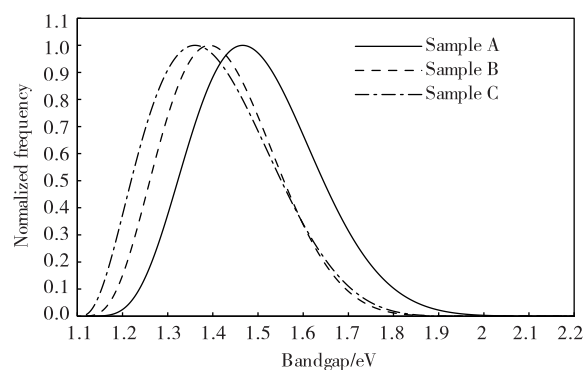


Fig.4 Simulated normalized bandgap distribution

annealed Si QD sample ( $V(O) : V(Si)$  ratio is 0.7) with 30 bilayers on Si substrate as shown on Figure 3. Kourkoutis et al. has reported that Si concentration in the SRO layer has influence on the size and shape of the QD<sup>[7]</sup>. For a high Si concentration sample, the QD size will correspond with the SRO layer thickness but its shape become ellipsoidal and has a wide size distribution. For a low Si concentration sample, the shape of QD is more spherical but the size is smaller than the SRO thickness. The Si concentration of the sample used in this work is relatively high and we can see that their sizes generally correspond with SRO thickness but have wide distribution. This is consistent with Kourkoutis's report. It will be a considerable issue for the practical application because such large bandgap distribution will induce undesirable band states and cause inhomogeneity of the material. However, the conductivity will be a problem if we reduce the Si concentration. Therefore, the optimal Si concentration is the key factor to realize uniform QDs with considerable conductivity and should be further investigated in such solid state Si QD samples.

### 3 Conclusion

Now we have the capability to quantitatively analyse the size distribution of sputter annealed Si QD samples from the PL spectra. We have seen that the size distribution is more widely spread compared to colloidal as reference. This may be mostly because of the distribution in horizontal direction and become prominent in higher silicon content samples. As well as this, with the number of layer increasing the spread becomes wider. This may be due to the penetration of nanocrystals in barrier layers. The wide distribution of QD size will cause the spread of bandgap and reduce the quantum confinement effect which limits the practical application of such materials.

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